

Niveostan[®]

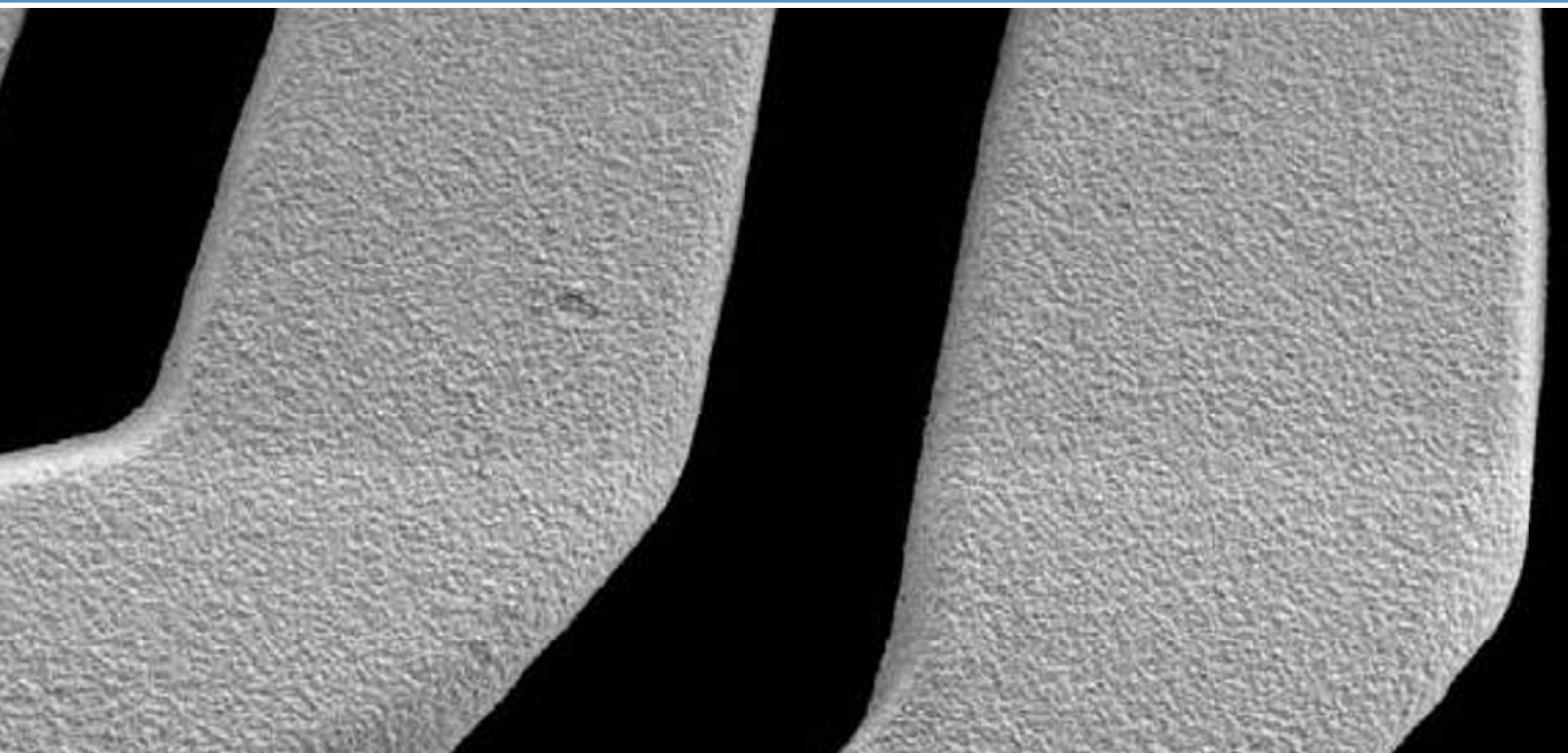
A product family for semibright, pure and large grained tin deposits



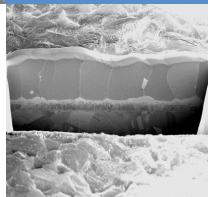
Electronics

Functional electronic coatings

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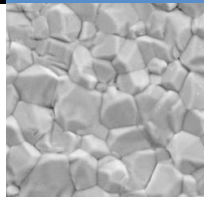
Niveostan[®] SL (Plus)



High and low speed

Universal solution for reel-to-reel and rack/barrel plating.
Deposition speed:
0.2 – 12 $\mu\text{m}/\text{min}$

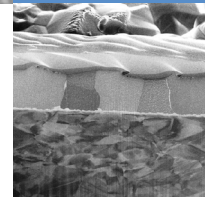
Niveostan[®] A1



Best uniformity

For the most demanding designs in rack plating.
Deposition speed:
0.5 – 2.5 $\mu\text{m}/\text{min}$

Niveostan[®] 200



Highest speed version

For the fastest deposition technology.
Deposition speed:
2 – 30 $\mu\text{m}/\text{min}$

Niveostan[®] product family

- Semibright deposits
- Large crystals with a brick like structure and a flatter surface morphology than standard matt deposits
- Qualified by major automotive customers
- Extremely low whisker propensity passing JESD201 etc.
- Available as low speed version for rack/barrel applications (about 0.2 $\mu\text{m}/\text{min}$) or high-speed versions that can deposit up to 30 $\mu\text{m}/\text{min}$ tin
- Ideally combined with our Protectostan[®] and SuperDip SN products to preserve excellent solderability
- Free of Fluoroborate and NPEs

Niveostan[®] – Pure and reliable tin deposits

Product	Niveostan [®] SL	Niveostan [®] SL Plus	Niveostan [®] A1	Niveostan [®] A200
Appearance	Semibright	Semibright	Semibright	Semibright
Application	Rack/Barrel	Reel to Reel	Rack/Barrel	Reel to Reel
Current density range ASD	0.5 – 3.0	5 – 25	1 – 5	5 – 60
Deposition speed $\mu\text{m}/\text{min}$	0.2 – 1.2	2.5 – 12.5	0.5 – 2.5	2.5 – 30
Grain size μm	3 – 10	3 – 10	3 – 10	3 – 10
Roughness RSAI %*	15 – 20	15 – 20	15 – 20	15 – 20
Carbon content ppm	< 25	< 25	< 25	< 25
Sulfur content	< 5	< 5	< 5	< 5
Solderability	Excellent	Excellent	Excellent	Excellent
Cutting edge	Qualified for automotive applications	Medium speed version qualified for automotive	Exceptional uniformity for all designs-even the most difficult ones	Highest deposition speed, qualified for automotive

* RSAI = Relative surface area increase compared to a totally flat surface, measured by interferometer microscope on connectors with 3 μm Sn

